

# **Ultra Shallow Junction Formation Using Diffusion from Suicides: I. Silicide Formation, Dopant Implantation and Depth Profiling**

Jiang H, Osburn CM, McGuire G.

Journal of the Electrochemical Society

1992; 139(1):196-206

## **ARTICLE IDENTIFIERS**

DOI: 10.1149/1.2069169

PMID: unavailable

PMCID: not available

## **JOURNAL IDENTIFIERS**

LCCN: not available

pISSN: 0013-4651

eISSN: not available

OCLC ID: not available

CONS ID: not available

US National Library of Medicine ID: not available

This article was identified from a query of the SafetyLit database.